



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re application of: Zhu et al.

Attorney Docket No.:
NOVLP090/NVLS-002888

Application No.: 10/733,858

Examiner: Not yet assigned

Filed: December 10, 2003

Group: 2812

Title: BIASED H₂ ETCH PROCESS IN
DEPOSITION-ETCH-DEPOSITION GAP
FILL

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on March 29, 2004 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

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Tara Hayden

REQUEST FOR CORRECTED FILING RECEIPT

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Sir:

Enclosed is a copy of the Filing Receipt for the above-identified patent application. Please reprint the Filing Receipt as follows and mail the corrected copy to the undersigned.

Change the Applicant "Jengyi Xu" to --Jengyi Yu--.

Since this is a Patent Office typographical error, no fee should be due. However, the Commissioner is authorized to charge any fees that may be due to Deposit Account 500388 (Order No. NOVLP090).

Respectfully submitted,
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/733,858	12/10/2003	2812	0.00	NOVL P090/NVLS002888	6	20	2

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CONFIRMATION NO. 7860

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OC000000012123155

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Applicant(s)

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Assignment For Published Patent Application

Novellus Systems, Inc.;

Domestic Priority data as claimed by applicant

Foreign Applications

If Required, Foreign Filing License Granted: 03/17/2004 BA

Projected Publication Date: Request for Non-Publication Acknowledged

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Early Publication Request: No

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Title

Biased H2 etch process in deposition-etch-deposition gap fill

Preliminary Class

438

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